Form PTO-1449

## U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

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PRIORITY SERIAL NO. 09/717,476

APPLICANT Harry Rosenberg

PRIORITY FILING DATE

PRIORITY GROUP

November 20, 2000

U.S. PATENT DOCUMENTS

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U.S. DEPARTMENT OF COMMERCE PRIORITY SERIAL NO. Form PTO-1449 ATTY. DOCKET NO. PATENT AND TRADEMARK OFFICE 34593 CON.1 09/717.476 LIST OF ART CITED BY APPLICANT APPLICANT Harry Rosenberg (Use several sheets if necessary) PRIORITY FILING DATE November 20, 2000 PRIORITY GROUP 2818 U.S. PATENT DOCUMENTS Date Subclass Filing Date \*Examiner Document Name Class Initial Number If Appropriate ΑB AC AD ΑE ΑF AG ΑH ΑI ΑJ ٩ĸ AL FOREIGN PATENT DOCUMENTS Class Subclass Translation Date Document Country Number Yes AM AN ΑU OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Albrecht, et al., "Modern Extraction of Tantalum and Niobium with Special Emphasis on the Production of High Purity Compounds," Conference Proceedings of Inter.Symp. On Tantalum and Niobium, 11/1988, Brussels, Belgium, 22 pages. PP ΑP Aichert et al., "Progresses in the Economical Production of Very Clean Refractory Metals and Alloys by Electron Beam Melting," Conference Proceedings on Progress in the Economical Production of Very Clean Refractory Metals and Alloys, 05/1985, Reutte, Austria, pages 863-877. Pierret et al., "Operation of Electron Beam Furnace for Melting Refractory Metals" page 208-217, Conference and date not known. AQ

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